

Title (en)

Process and apparatus for decontamination using ion etching.

Title (de)

Verfahren und Vorrichtung zur Dekontaminierung durch Ionenätzen.

Title (fr)

Procédé et dispositif de décontamination par décapage ionique.

Publication

**EP 0454584 B1 19950802 (FR)**

Application

**EP 91401101 A 19910425**

Priority

FR 9005417 A 19900427

Abstract (en)

[origin: EP0454584A1] According to the invention, in order to decontaminate an object (2) whose surface is contaminated by a contaminating material, at least a part of the surface is covered with an enclosure (6), this part, taken as a target, is etched by cathodic sputtering and the contaminating material thus removed is collected on a substrate (12) contained in the enclosure. Application to the decontamination of objects contaminated with radioactive materials. <IMAGE>

IPC 1-7

**G21F 9/00**

IPC 8 full level

**G21F 9/28** (2006.01); **B08B 7/00** (2006.01); **C23G 5/00** (2006.01); **G21F 9/00** (2006.01)

CPC (source: EP)

**B08B 7/0035** (2013.01); **C23G 5/00** (2013.01); **G21F 9/005** (2013.01)

Cited by

US2021272715A1; WO9822231A1

Designated contracting state (EPC)

BE CH DE FR GB IT LI NL

DOCDB simple family (publication)

**EP 0454584 A1 19911030**; **EP 0454584 B1 19950802**; DE 69111671 D1 19950907; DE 69111671 T2 19960404; FR 2661544 A1 19911031; FR 2661544 B1 19940527; JP 2892857 B2 19990517; JP H04230898 A 19920819

DOCDB simple family (application)

**EP 91401101 A 19910425**; DE 69111671 T 19910425; FR 9005417 A 19900427; JP 9598391 A 19910426